and the formates of Ca, Cd, and Sr have elastic and ther- 
moplastic properties. Bivalent metal formates could be 
used as precursors for the production of catalysts 
because they show excellent miscibility in the solid state, 
i.e., they form mixed crystals that dissociate at relatively 
low temperatures (about 300 °C) to form the respective 
oxides and mixed oxides. There are also additional 
smaller-scale uses of metal formates. The wide interest 
in the applications and uses of metal formates will lead 
to an interest in seeking methods for the preparation of 
these materials. Solubility data for the metal formates 
will be helpful in devising the methods of preparation. 
Therefore, this volume has been prepared to present and 
evaluate solubility data for the binary, ternary and multi-
component systems containing metal formates in aque-
ous and in nonaqueous solutions.

Mycotoxins and Phycotoxins in 
Perspective at the Turn of the Millennium

Willem J. de Koe, Robert A. Samson, Hans P. van 
Egmond, John Gilbert and Myrna Sabino, (eds.) W.J. 

This book contains symposium keynote lecture, plenary 
lectures which introduce each topic area, and con-
tributed oral papers presented at the Xth International 
IUPAC Symposium on Mycotoxins and Phycotoxins, 
held from 21-25 May 2000 in Guarujá, Brazil.

Brazil made history in the mycotoxin area when afla-
toxin was detected for the first time in Brazilian peanut 
meal exported to England, explained M. Sabino. From 
that time, a new field of research was created: mycotoxi-
cology. After 40 years, the opportunity emerged to gath-
er the renowned authorities in the area to discuss the 
problem in where this contaminant was first detected. 
Being a country with continental dimensions, Brazil is 
subject to climatic diversities, consequently, the possibil-
ity of producing mycotoxins other then the aflatoxins. 
Fortunately, various research groups, governmental agen-
cies, universities and industries are working together to 
minimize the problem and today the level of contamina-
tion is no longer what is was used to get together and dis-
cuss various topics such as control and/or prevention, 
new methods of detection, decontamination, etc.

Nomenclature of Organic Compounds. 
Principles and Practice. 2nd edition

Robert B. Fox and Warren H. Powell 
American Chemical Society and Oxford University 

The authors served for many years as members of and 
consultants to the American Chemical Society 
Nomenclature Committee and to several IUPAC 
Nomenclature Commissions. They stress the need for 
unambiguous communication among organic chemists 
and for understanding of names for chemical structures 
and chemical substances.

The book focuses on the methods and their application 
in the naming of organic compounds, stressing the 
relationship between structure and name. The first part 
is a general overview of organic nomenclature. It 
includes origin and evolution, conventions, and methods 
of organic nomenclature, and a very useful chapter on 
common errors, pitfalls, and misunderstandings. The 
second part uses the concepts from the first part to 
answer the question “how do I name this compound?”.
Every common class of organic compounds is covered, from simple hydrocarbons, hetero compounds, acids, aldehydes, alcohols, amides, and amines to nitrogen, sulfur, phosphorus, silicon, boron, and organometallic compounds, polymers, natural products, stereoisomers, isotopically modified compounds, radicals, and ions. Throughout the book, the concepts and methods of the IUPAC recommendations are compared with rules used by Chemical Abstracts Service and other sources. Appendices contain most useful lists of substituent prefixes and common endings, and a glossary of terms.

Reports from Conferences

Plasma Chemistry

by Steven L. Girshick

The 15th International Symposium on Plasma Chemistry, ISPC-15, was held in Orléans, France, from 9-13 July 2001. The Symposium was hosted by the laboratory GREMI (Groupe de Recherche sur l’Énergie des Milieux Ionisés) at the University of Orléans, and was organized by an International Organizing Committee and a Local Organizing Committee, chaired respectively by A. Bouchoule and J. M. Pouvésle, both of GREMI. The 610 registered attendees came from 40 countries. Countries with the highest number of attendees included France (218), Japan (90), Germany (48), Russia (32), the United States (32), Czech Republic (31), Canada (26), Italy (20), Poland (16) and the Netherlands (12). The Symposium was preceded by the biennial International Summer School on Plasma Chemistry, held 4-6 July, and a Workshop on Industrial Applications of Plasma Processing, on 7 July, both of which were well attended.

The high quality of the presentations and the range of topics demonstrated the extraordinary vitality of the field of plasma chemistry. Over 550 papers were presented at the symposium, including 133 oral presentations and 420 posters. Presentations were grouped into major topical areas, which included fundamentals of and basic processes in each of thermal plasmas and non-equilibrium plasmas; sources, diagnostics and modeling in each of atmospheric pressure non-equilibrium plasmas, thermal plasmas and low-pressure plasmas; plasma chemical vapor deposition of silicon-based compounds; inorganic films and hard coatings; plasma deposition and treatment of polymers; etching and microtechnology; plasma sprays and thermal plasma material processing; clusters, particles and powders; environmental applications of each of thermal plasmas and non-equilibrium plasmas; plasma chemical synthesis/engineering; and laser-based technologies and plasma light sources. The full conference proceedings, edited by A. Bouchoule, J. M. Pouvešle, A. L. Thomann, J. M. Bouchire and E. Robert, comprise eight volumes and more than 3000 pages.

There were seven plenary lectures, given by C. H. Kruger, Stanford University, US, on non-equilibrium discharges in air at atmospheric pressure; D. C. Schram, Eindhoven University of Technology, the Netherlands, on plasma processing and chemistry; M. Sekine, Association of Super Advanced Electronics Technologies, Japan, on future plasma technologies in ULSI processing; J. Heberlein, University of Minnesota, US, on new approaches in thermal plasma technology; S. De Benedictis, University of Bari, Italy, on energy transfers by long-lived species in glows and afterglows; P. Roca i Cabarrocas, École Polytechnique, France, on plasma production of polymorphous silicon thin films; and M. Moisan, University of Montreal, Canada, on plasma sterilization. The plenary and invited papers will be published in Pure and Applied Chemistry, edited by A. Bouchoule.

The conference banquet was held at the magnificent Chateau de Blois. At the banquet the Plasma Chemistry Award was presented to Prof. Pierre Fauchais, of the University of Limoges, France. The Plasma Chemistry Award is the major award of the plasma chemistry community for career achievement. Prof. Fauchais was recognized for his outstanding contributions in the areas of thermal plasmas, plasma spraying, optical diagnostics, and modeling. In 1968 Prof. Fauchais founded the group on “Procédés de traitements de surface,” which is part of the CNRS laboratory SPCTS at the University of Limoges. Prof. Fauchais continues to direct this group, which has educated a large number of plasma scientists and engineers. In addition he has a distinguished record of service to the plasma chemistry community, having organized a number of conferences and having served on the IUPAC Subcommittee on Plasma Chemistry.

Best Paper Awards were presented to three young plasma scientists: Nicolas Gherardi, Université Paul Sabatier, Toulouse, France, for his paper on light emission in a glow dielectric barrier discharge in nitrogen; Matthias Meier, Max Planck